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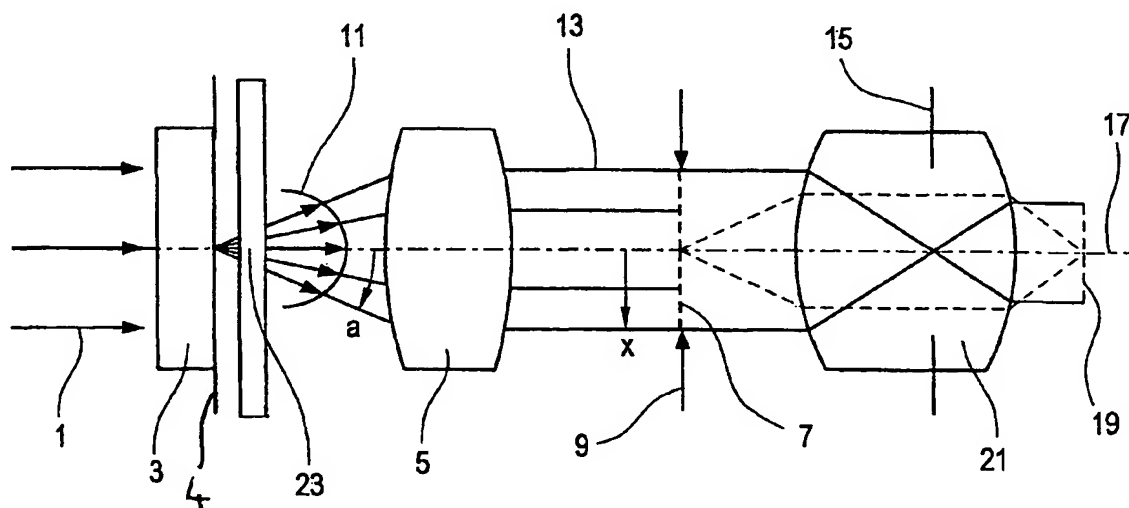
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- (71) Applicant (for all designated States except US): **CARL ZEISS SMT AG** [DE/DE]; Carl-Zeiss-Stasse 22, 73447 Oberkochen (DE).
- (72) Inventors; and
(75) Inventors/Applicants (for US only): **SINGER, Wolfgang** [DE/DE]; Egerlandstrasse 45, 73431 Aalen (DE). **WIET-ZORREK, Joachim** [DE/DE]; Silcherstrasse 61, 73430 Aalen (DE). **HAINZ, Joachim** [DE/DE]; Zeppelinstrasse 49, 73430 Aalen (DE). **WEIRAUCH, Gabriele** [DE/DE]; Bischof-Fischer-Strasse 47/1, 73430 Aalen (DE). **MAUL, Manfred** [DE/DE]; Elchweg 29, 73434 Aalen (DE).
- (74) Agent: **WEITZEL & PARTNER**; Friedenstr. 10, 89522 Heidenheim (DE).
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(54) Title: AN ILLUMINATION SYSTEM FOR MICROLITHOGRAPHY



(57) Abstract: The present invention relates to an illumination system for microlithography, especially for wavelengths ≤ 193 nm, especially preferably for EUV lithography for illuminating a field in a field plane (9) with at least one optical integrator (3) which splits up a light bundle emitted by a light source into a plurality of light channels each having a light intensity, characterized in that a filter (23) is provided in the light path from the light source to the field plane (9), with the filter comprising filter elements which are configured in such a way that the light intensity of at least one light channel is reduced in the light path after the filter element.

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